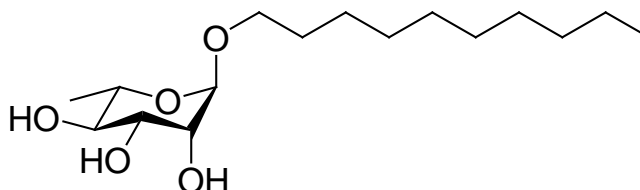




Product Name: Decyl Rhamnoside (decyl- α -L-rhamnopyranoside) >95%

Product Number: RhE-C10



Molecular Formula: C₁₆H₃₂O₅ **MW:** 304.42 **CAS:** N/A

Solubility: Water Soluble ~35 mg/L, soluble in most organic solvents.

Storage: Room temperature or below

Critical Micelle Concentration (CMC): ~344 μ M

Surface Tension (γ CMC): ~29 mN/m

pH = 6 – 8 in water

Estimated HLB: **~10 (Griffin Method) and ~8.5 (Davies Method)**. Generally classified as an O/W emulsifying agent.

Field of Interest: Decyl rhamnoside surfactants are suitable for use in cosmetics, including in anti-aging creams, soaps, and other skin or facial treatments. Use as surfactants in cleaning applications, such as surface cleaning, has also been studied. Agriculture uses are known, as well as bioremediation, and enhanced oil recovery projects.

General: Decyl rhamnoside (like many of its natural rhamnose-based derivatives) is a good foaming and wetting agent, with the ability to increase the aqueous solubility of hydrophobic compounds, making them excellent solubilizing and emulsifying agents for diverse applications.

Hazardous Properties and Cautions: The toxicological and pharmacological properties of this compound are not fully known. For further information see the SDS on request. Decyl Rhamnoside is manufactured and shipped only in small quantities, intended for research and development in a laboratory utilizing prudent procedures for handling chemicals of unknown toxicity, under the supervision of persons technically qualified to evaluate potential risks and authorized to enforce appropriate health and safety measures. As with all research chemicals, precautions should be taken to avoid unnecessary exposures or risks.

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